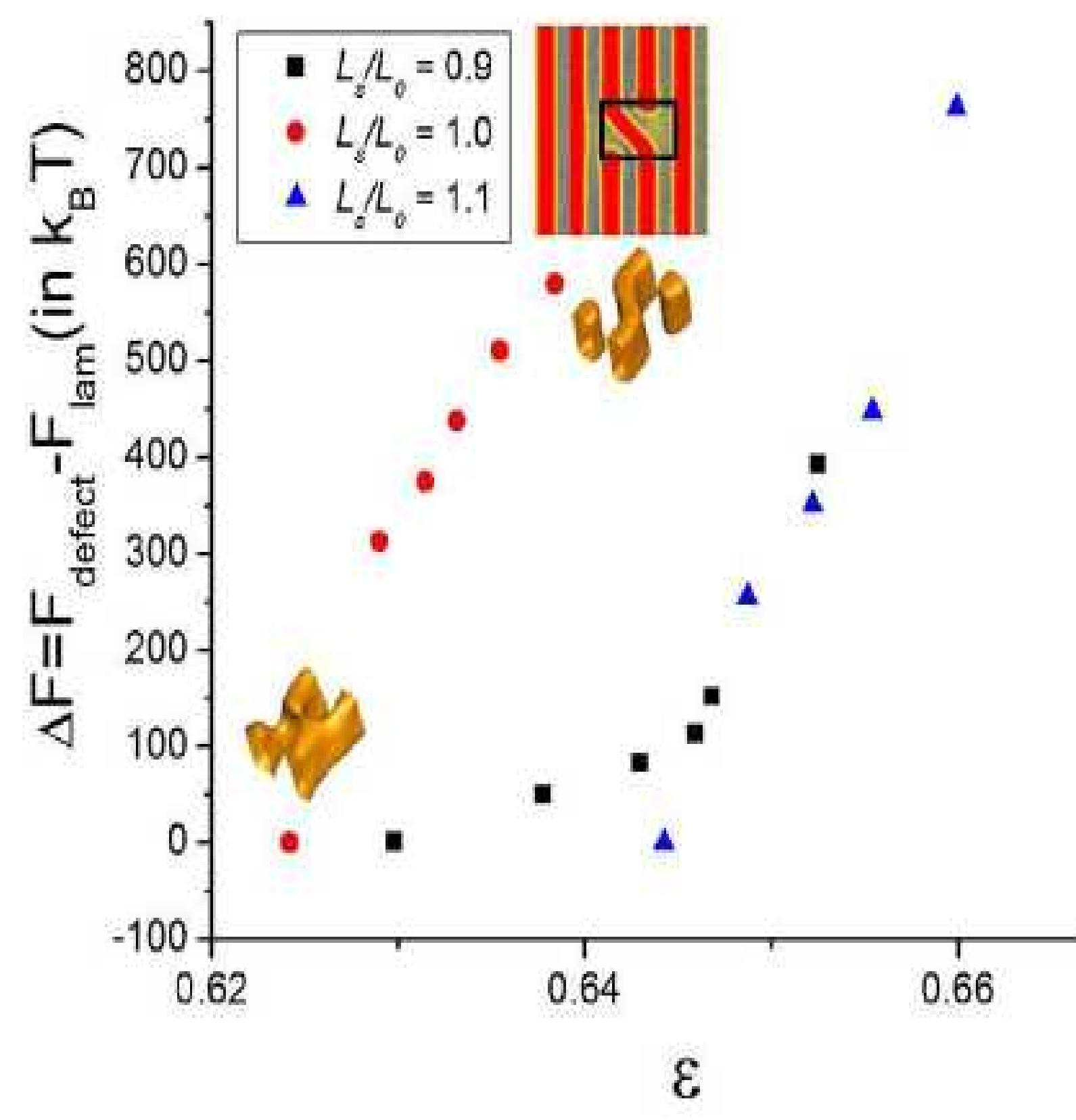
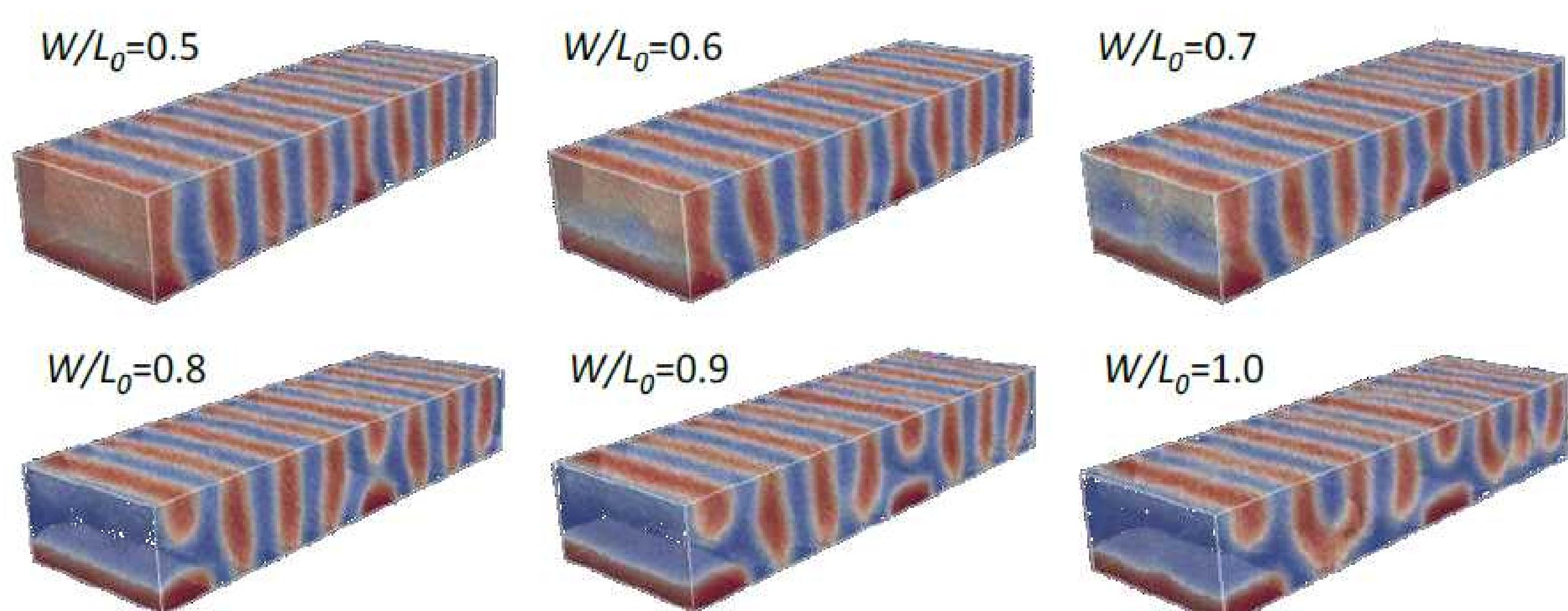
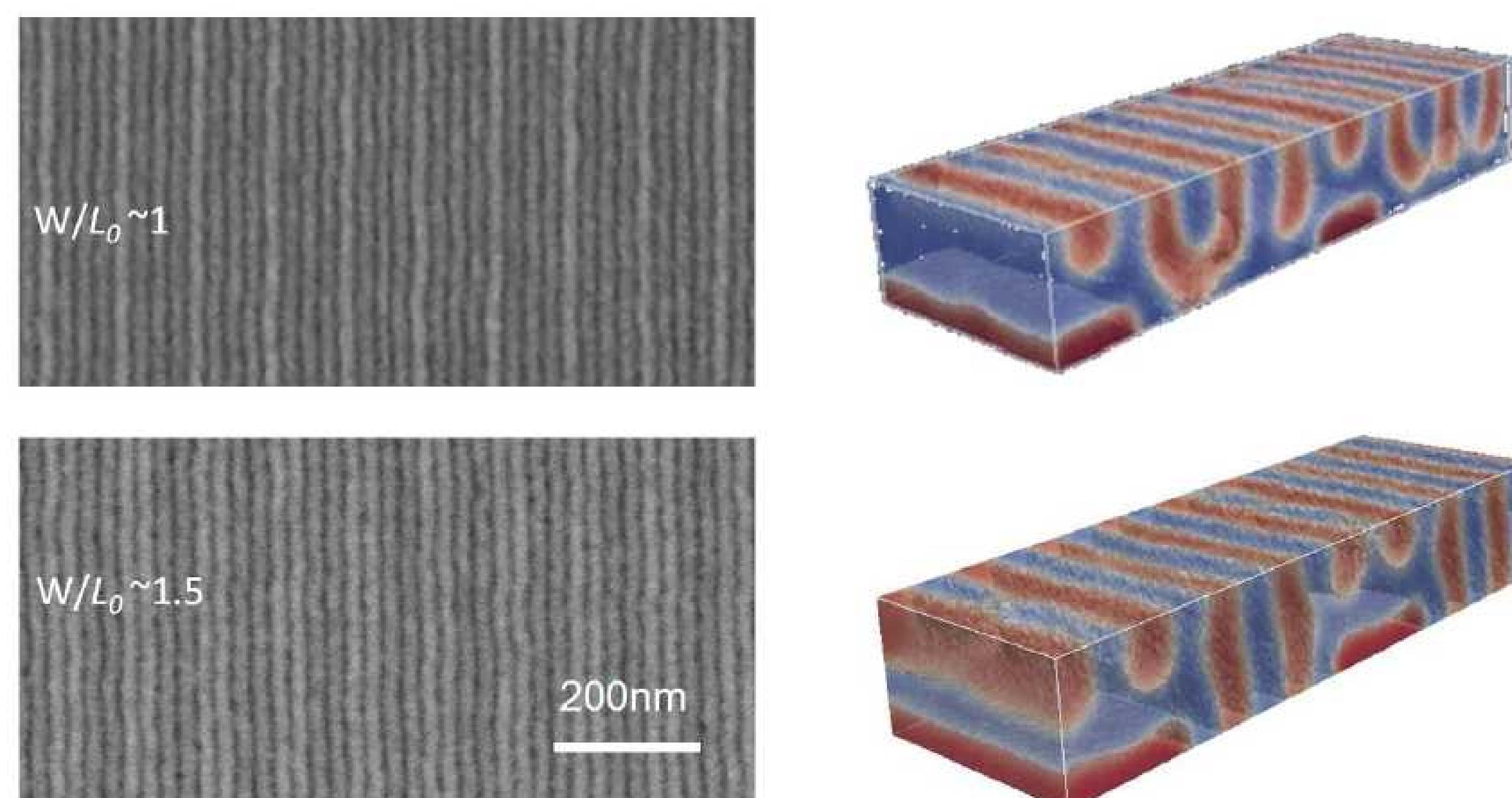
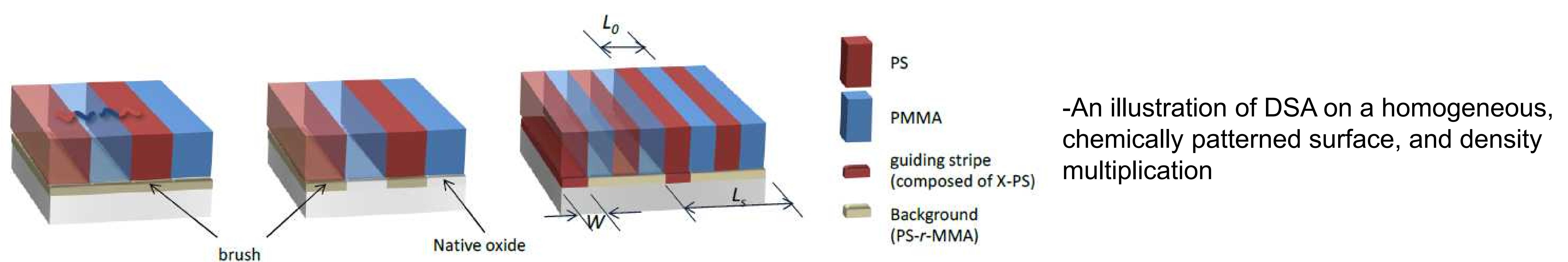


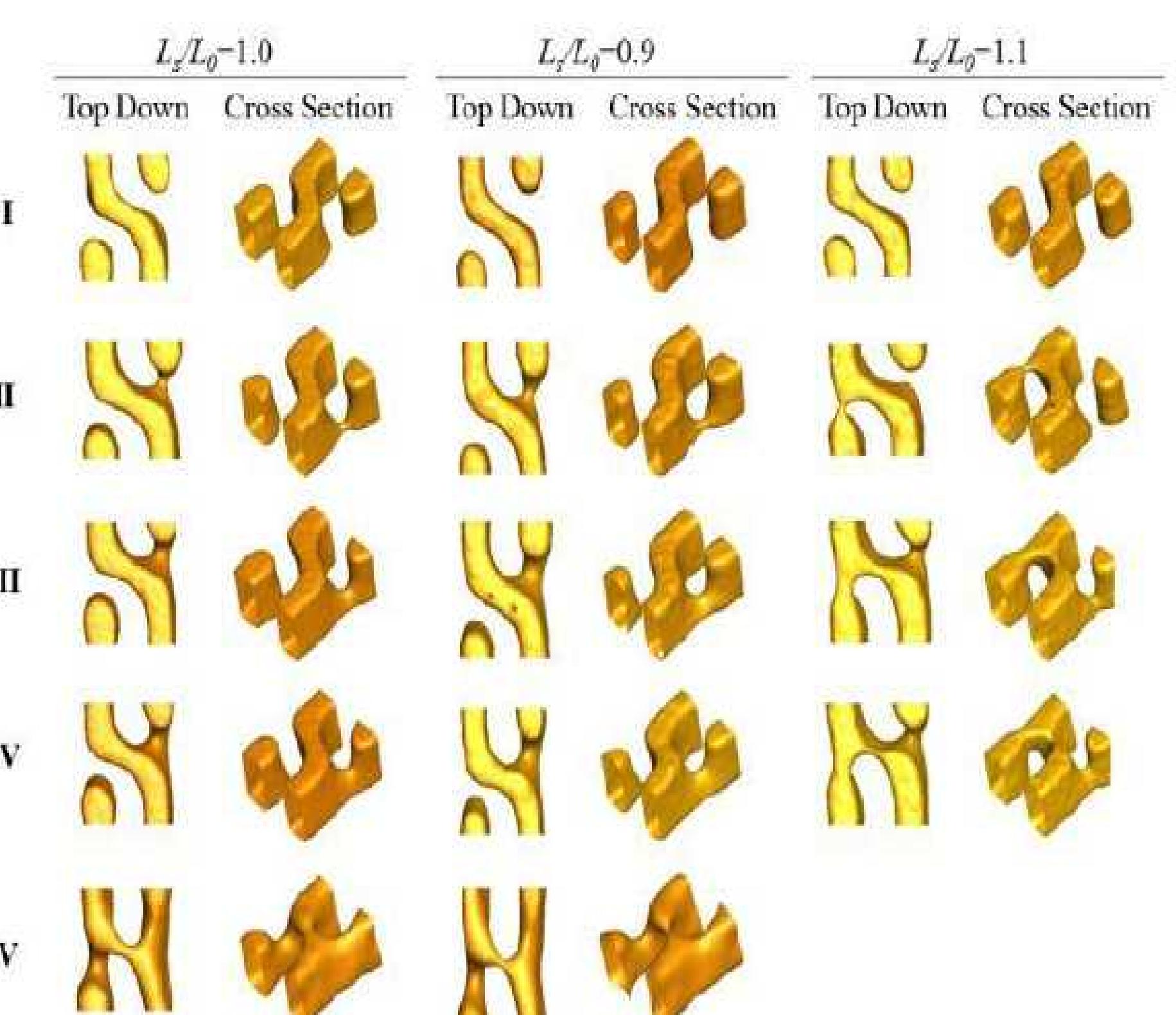
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Directed self-assembly (DSA) of block copolymers (BCP) is a thermodynamic equilibration process of the entire BCP film system, including the top surface of the film and the interface of the BCP with the underlying, patterned substrate. In order to study the optimum patterned substrate conditions for DSA with density multiplication, we analyzed the effect of the chemistry of the chemical pattern and the density multiplication factor on assembly quality. Free energy calculations were also performed on jog defects.



$$\varepsilon = \frac{1}{V} \int_{\text{defect}} (\phi_A - \phi_B)^2 dV$$



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